

12 and said counter electrode to thereby make a display, wherein said color filter is formed on a
13 passivation film for protecting said thin film transistors; and said pixel electrode is arranged
14 on said color filter and connected to said thin film transistors through a contact hole provided
15 in said passivation film and said color filter; and

16 gate insulating layers of said thin film transistors and said passivation film being
17 removed in a light transmission region within pixels surrounded by said scanning lines and
18 said signal lines.

1 2. (Amended) An active matrix liquid crystal display device comprising:

2 a first substrate and a second substrate, at least one of the first and second substrate
3 being transparent;

4 a liquid crystal layer formed between the first and second substrate;

5 a color filter;

6 an overcoat layer protecting said color filter, said first substrate including a plurality
7 of scanning lines;

8 a plurality of signal lines crossing the plurality of scanning lines in a matrix manner;

9 a plurality of thin film transistors formed at intersections of the scanning lines and the
10 signal lines, respectively;

11 a pixel electrode connected to said thin film transistors, said second substrate
12 including a counter electrode, liquid crystal molecules being driven by an electric field
13 between said pixel electrode and said counter electrode to thereby make a display, wherein
14 said color filter is formed on a passivation film for protecting said thin film transistors,
15 said overcoat layer is formed on said color filter, and said pixel electrode is arranged on said
16 overcoat layer and connected to said thin film transistors through a contact hole provided in
17 said passivation film, said color filter and said overcoat layer; and

18 gate insulating layers of said thin film transistors and said passivation film are
19 removed in a light transmission region within pixels surrounded by said scanning lines and
20 said signal lines.

1 6. (Amended) A method of manufacturing an active matrix liquid crystal display device, the

2 method comprising:

3 forming a plurality of scanning lines on a first substrate;

4 forming a plurality of signal lines crossing the plurality of scanning lines in a matrix
5 manner;

6 forming a plurality of thin film transistors at intersections of the plurality of scanning
7 lines and the plurality of signal lines, respectively;

8 forming a pixel electrode connected to said thin film transistors;

9 forming a counter electrode on a second substrate;

10 injecting a liquid crystal between said first substrate and said second substrate and
11 sealing the liquid crystals,

12 wherein said method further comprises:

13 forming a passivation film to protect each of said thin film transistors;

14 removing part of a gate insulating layer and said passivation film of each of
15 said thin film transistors in a region surrounded by said signal lines and said scanning
16 lines;

17 forming a color filter made of a photosensitive color resist; and

18 forming a transparent conductive film.

1 7. (Amended) A method of manufacturing an active matrix liquid crystal display device, the
2 method comprising :

3 forming a plurality of scanning lines on a first substrate;

4 forming a plurality of signal lines crossing the plurality of scanning lines in a matrix
5 manner;

6 forming a plurality of thin film transistors at intersections of the plurality of scanning
7 lines and the plurality of signal lines, respectively;

8 forming a pixel electrode connected to said thin film transistors;

9 forming a counter electrode on a second substrate;

10 injecting liquid crystal between said first substrate and said second substrate and
11 sealing the liquid crystals,

12 wherein said method further comprises:

13 forming a passivation film to protect each of said thin film transistors;
14 removing part of a gate insulating layer and said passivation film of each of
15 said thin film transistors in a region surrounded by said signal lines and said scanning
16 lines;
17 forming a color filter made of a photosensitive color resist;
18 forming an overcoat layer on said color filter;
19 patterning said overcoat layer;
20 forming a contact hole by patterning said color filter while using said overcoat
21 layer as a mask; and
22 forming a transparent conductive film.

Please add the following new claims.

-- 11. An active matrix liquid crystal display device, including:

a plurality of pixels, each of said pixels comprising:
a transistor;
a passivation film formed to cover said transistor said passivation film having
a first hole exposing an electrode of said transistor and a pixel opening;
a color filter formed to fill said pixel opening of said passivation film, said
color filter having a second hole; and
a pixel electrode formed to cover said color filter and to be connected to the
electrode of said transistor through said first and second holes.

12. The device as claimed in claim 11, wherein said color filter has a substantially
flat surface so that a first portion of said color filter filling said pixel opening is larger in
thickness than a second portion of said color filter covering said passivation film.

13. The device as claimed in claim 12, wherein said transistor includes a gate
insulating film, said gate insulating film having a third hole that is formed correspondingly to
said pixel opening of said passivation film and is filled with said color filter.

1 14. The device as claimed in claim 12, wherein said color filter is extended to
2 cover said transistor with an intervention of said passivation film.

1 15. The device as claimed in claim 12, wherein each of said pixels further
2 comprises an overcoat layer inserted between said color filter and said pixel electrode.

1 16. The device as claimed in claim 12, wherein each of said pixels further
2 comprises a signal line connected to said transistor, said color filter provided for one of said
3 pixels being extended to and terminated on the signal line connected to an adjacent one of
4 said pixels with an intervention of a part of said passivation film.

1 17. A method of manufacturing an active matrix liquid crystal display device, the method
2 comprising:
3 forming a plurality of pixels, said forming of said plurality of pixels comprising, for
4 each of said pixels:

5 providing a transistor;
6 forming a passivation film to cover said transistor;
7 forming a first hole in said passivation film exposing an electrode of said
8 transistor and a pixel opening;
9 forming a color filter to fill said pixel opening of said passivation film, said
10 color filter having a second hole; and
11 forming a pixel electrode to cover said color filter and connect to the electrode
12 of said transistor through said first and second holes.

1 18. The method as claimed in claim 17, wherein said color filter has a substantially
2 flat surface so that a first portion of said color filter filling said pixel opening is larger in
3 thickness than a second portion of said color filter covering said passivation film.

1 19. The method as claimed in claim 18, wherein said transistor includes a gate

2 insulating film, said gate insulating film having a third hole that is formed correspondingly to
3 said pixel opening of said passivation film and is filled with said color filter.

1 20. The method as claimed in claim 18, wherein said color filter is extended to
2 cover said transistor with an intervention of said passivation film.

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1 21. The method as claimed in claim 18, further comprising, for each of said pixels, inserting
2 an overcoat layer between said color filter and said pixel electrode.

1 22. The method as claimed in claim 18, further comprising, for each of said pixels, providing
2 a signal line connected to said transistor, said color filter provided for one of said pixels being
3 extended to and terminated on the signal line connected to an adjacent one of said pixels with
4 an intervention of a part of said passivation film. --
